



UNITED STATES PATENT AND TRADEMARK OFFICE

UNITED STATES DEPARTMENT OF COMMERCE
United States Patent and Trademark Office
Address: COMMISSIONER FOR PATENTS
P.O. Box 1450
Alexandria, Virginia 22313-1450
www.uspto.gov

APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/596,126	05/31/2006	Euijoon Yoon	21302/0204309-US0	2554
7278	7590	06/23/2008	EXAMINER	
DARBY & DARBY P.C. P.O. BOX 770 Church Street Station New York, NY 10008-0770			CRAWFORD, LATANYA N	
			ART UNIT	PAPER NUMBER
			2813	
			MAIL DATE	
			06/23/2008	PAPER
			DELIVERY MODE	

Please find below and/or attached an Office communication concerning this application or proceeding.

The time period for reply, if any, is set in the attached communication.

Office Action Summary	Application No.	Applicant(s)	
	10/596,126	YOON ET AL.	
	Examiner	Art Unit	
	LATANYA CRAWFORD	2813	

-- The MAILING DATE of this communication appears on the cover sheet with the correspondence address --

Period for Reply

A SHORTENED STATUTORY PERIOD FOR REPLY IS SET TO EXPIRE 3 MONTH(S) OR THIRTY (30) DAYS, WHICHEVER IS LONGER, FROM THE MAILING DATE OF THIS COMMUNICATION.

- Extensions of time may be available under the provisions of 37 CFR 1.136(a). In no event, however, may a reply be timely filed after SIX (6) MONTHS from the mailing date of this communication.
- If NO period for reply is specified above, the maximum statutory period will apply and will expire SIX (6) MONTHS from the mailing date of this communication.
- Failure to reply within the set or extended period for reply will, by statute, cause the application to become ABANDONED (35 U.S.C. § 133). Any reply received by the Office later than three months after the mailing date of this communication, even if timely filed, may reduce any earned patent term adjustment. See 37 CFR 1.704(b).

Status

1) Responsive to communication(s) filed on 18 March 2008.
 2a) This action is **FINAL**. 2b) This action is non-final.
 3) Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under *Ex parte Quayle*, 1935 C.D. 11, 453 O.G. 213.

Disposition of Claims

4) Claim(s) 11-23 is/are pending in the application.
 4a) Of the above claim(s) 16 is/are withdrawn from consideration.
 5) Claim(s) _____ is/are allowed.
 6) Claim(s) 11-15 and 17-23 is/are rejected.
 7) Claim(s) _____ is/are objected to.
 8) Claim(s) _____ are subject to restriction and/or election requirement.

Application Papers

9) The specification is objected to by the Examiner.
 10) The drawing(s) filed on 31 May 2006 is/are: a) accepted or b) objected to by the Examiner.
 Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a).
 Replacement drawing sheet(s) including the correction is required if the drawing(s) is objected to. See 37 CFR 1.121(d).
 11) The oath or declaration is objected to by the Examiner. Note the attached Office Action or form PTO-152.

Priority under 35 U.S.C. § 119

12) Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f).
 a) All b) Some * c) None of:
 1. Certified copies of the priority documents have been received.
 2. Certified copies of the priority documents have been received in Application No. _____.
 3. Copies of the certified copies of the priority documents have been received in this National Stage application from the International Bureau (PCT Rule 17.2(a)).

* See the attached detailed Office action for a list of the certified copies not received.

Attachment(s)

1) <input checked="" type="checkbox"/> Notice of References Cited (PTO-892)	4) <input type="checkbox"/> Interview Summary (PTO-413)
2) <input type="checkbox"/> Notice of Draftsperson's Patent Drawing Review (PTO-948)	Paper No(s)/Mail Date. _____ .
3) <input type="checkbox"/> Information Disclosure Statement(s) (PTO/SB/08)	5) <input type="checkbox"/> Notice of Informal Patent Application
Paper No(s)/Mail Date _____.	6) <input type="checkbox"/> Other: _____ .

DETAILED ACTION

1. This office action is in response to the correspondence filed on 03/18/2008. The objections made to the specification and claims have been withdrawn as a result of the amendment submitted providing corrections to the specification and claims 11, 12, 14, 16-19 & 22. Examiner acknowledges cancelled claim 16. Currently, claims 11-15 & 17-23 are pending.

Claim Rejections - 35 USC § 102

2. The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless –

(b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States.

3. Claims 11, 17, 18, & 20-22 are rejected under 35 U.S.C. 102(b) as being anticipated by Nakamura (US pub no.2003/0015724 A1).

Regarding claim 11, Nakamura et al. discloses a nitride semiconductor light emitting device comprising: a substrate 11; at least one nitride semiconductor layer grown on the substrate and including a top layer of $\text{Al}_x\text{Ga}_y\text{In}_{1-x-y}\text{N}$ ($0 \leq x \leq 1$, $0 < y \leq 1$, $0 < x+y \leq 1$) 15 [0043]; a single quantum well layer 16 grown on the top layer of $\text{Al}_x\text{Ga}_y\text{In}_{1-x-y}\text{N}$ ($0 \leq x \leq 1$, $0 < y \leq 1$, $0 < x+y \leq 1$) 15 [0044], the quantum well layer being made of In-rich InGaN resulting from the lattice mismatch with the top layer of $\text{Al}_x\text{Ga}_y\text{In}_{1-x-y}\text{N}$ ($0 \leq x \leq 1$, $0 < y \leq 1$, $0 < x+y \leq 1$) layer an Ga in the In- rich InGaN being mainly supplied from the top layer of $\text{Al}_x\text{Ga}_y\text{In}_{1-x-y}\text{N}$ ($0 \leq x \leq 1$, $0 < y \leq 1$, $0 < x+y \leq 1$)

[0044][0075]; and an additional nitride semiconductor layer 101 grown on the quantum well layer and having a band gap energy higher than that of the quantum well layer; Since Nakamura et al. teaches that the quantum well layer has a smaller band gap than that of layer 15 and 101, this means that the quantum well layer has a an indium content higher than layer 15 and 101. This satisfies the limitation: wherein the single quantum well layer comprises an In-rich region, a first compositional grading region with In content increasing between the top layer of $\text{Al}_x\text{Ga}_y\text{In}_{1-x-y}\text{N}$ ($0 \leq x \leq 1$, $0 < y \leq 1$, $0 < x+y \leq 1$) and the In-rich region [0044], and second compositional grading region with In content decreasing between the In-rich region and the additional nitride semiconductor layer [0044].

Regarding claim 17, Nakamura et al. discloses wherein the additional nitride semiconductor 101 is formed of $\text{Al}_y\text{Ga}_{1-y}\text{N}$ ($0 \leq y \leq 1$) [0048].

Regarding claim 18, Nakamura et al. discloses further comprising at least one barrier layer of $\text{Al}_y\text{Ga}_{1-y}\text{N}$ ($0 \leq y \leq 1$) layer 103 [0054] and having a band gap energy higher than that of the additional nitride semiconductor layer 101[0048]. Since, layer 101 may have some In content, and layer 103 is preferably AlGaN, the band gap of layer 103 will be higher since it lacks In content.

Regarding claim 20, Nakamura et al. discloses wherein the quantum well layer and the at least barrier layer of $\text{Al}_y\text{Ga}_{1-y}\text{N}$ ($0 \leq y \leq 1$) to form a multi-quantum well structure [0045].

Regarding claim 21, Nakamura et al. discloses wherein the pairs of the quantum well and the at least barrier layer of $\text{Al}_y \text{Ga}_{1-y}\text{N}$ ($0 \leq y \leq 1$) equal to or less than 100 pairs [0045].

Regarding claim 22, Nakamura et al. discloses herein the top layer 15 of $\text{Al}_x\text{Ga}_y\text{In}_{1-x-y}\text{N}$ ($0 \leq x \leq 1$, $0 < y \leq 1$, $0 < x+y \leq 1$) is GaN [0043].

Claim Rejections - 35 USC § 103

4. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negated by the manner in which the invention was made.

5. Claims 12, 14, 15, 19 & 23 are rejected under 35 U.S.C. 103(a) as being unpatentable over Nakamura (US pub no.2003/0015724 A1) in view of Tysoe (US Pub no. 2004/0195598 A1).

Regarding claim 12, Nakamura et al. discloses all the claim limitations of claim 11 but fails to teach wherein the quantum well layer is formed of $\text{In}_x\text{Ga}_{1-x}\text{N}$ and x in the In-rich region of the quantum well layer is equal to or more than 0.6.

However, Tysoe et al. teaches wherein the quantum well layer 8 is formed of $\text{In}_x\text{Ga}_{1-x}\text{N}$ and x in the In-rich region of the quantum well layer is equal to or more than 0.6 [0045]. It would have been obvious to one of ordinary skill in the art at the time of the invention to modify the semiconductor light emitting device of Nakamura et al. with

the quantum well layer is formed of $\text{In}_x\text{Ga}_{1-x}\text{N}$ and x in the In-rich region of the quantum well layer is equal to or more than 0.6 taught by Tysoe et al. since doing so would provide a preferred excitation of a GaN light emitting diode

Regarding claim 14, Tysoe et al. discloses wherein the quantum well layer 8 is formed of $\text{In}_x\text{Ga}_{1-x}\text{N}$ and x in the In-rich region of the quantum well layer is within a range of 0.5 to 0.8 [0045].

Regarding claim 15, Tysoe et al. discloses wherein the thickness of the quantum well 8 is equal to or less than 2nm [0046].

Regarding claim 19, Nakamura et al. discloses wherein the at least one barrier layer of $\text{Al}_y\text{Ga}_{1-y}\text{N}$ ($0 \leq y \leq 1$) that is not greater than 150 angstroms(15 nm) except having a thickness equal to or less than 5 nm. Prior art reference that discloses a range encompassing a somewhat narrower claimed range is sufficient to establish a *prima facie case of obviousness.*" *In re Peterson*, 315 F.3d 1325, 1330, 65 USPQ2d 1379, 1382-83 (Fed. Cir. 2003).MPEP 2144.05

Regarding claim 23, Nakamura et al. discloses x in the In-rich region of the quantum well layer 8 is equal to or less than 0.7 [0045].

6. Claim 13 is rejected under 35 U.S.C. 103(a) as being unpatentable over Nakamura (US pub no.2003/0015724 A1) in view of Yamada (US Pub no. 2003/0209704 A1).

Regarding claim 13, Nakamura et a. discloses all the claim limitations of claim 11 but fails to teach wherein the quantum well layer is grown using an In source and a

nitrogen source, and the thickness of the quantum well is reduced by growth interruption which is performed by supplying the nitrogen source with the supply of the In source intercepted to flatten the surface of the quantum well layer.

However, Yamada et al. teaches the quantum well layer having a flattened surface [0030]. It would have been obvious to one of ordinary skill in the art at the time of the invention to modify the semiconductor light emitting device of Nakamura et al. with the quantum well layer having a flattened surface taught by Yamada et al. since doing so improves luminous efficiency. The limitations: grown using an In source and a nitrogen source, and the thickness of the quantum well is reduced by growth interruption which is performed by supplying the nitrogen source with the supply of the In source intercepted are not given patentable weight. "Even though product -by[-] process claims are limited by and defined by the process, determination of patentability is based upon the product itself. The patentability of a product does not depend on its method of production. If the product in product-by-process claim is the same as or obvious from a product of the prior art, the claim is unpatentable even though the prior product is made by a different process." *In re Thorpe*, 227 USPQ 964, 966 (Fed. Cir. 1985)(citations omitted). A "product by process" claim is directed to the product per se, no matter how actually made, *In re Hirao and Sato et al.*, 190 USPQ 15 at 17 (CCPA 1976) (footnote 3). See also *In re Brown and Saffer*, 173 USPQ 685 (CCPA 1972); *In re Luck and Gainer*, 177 USPQ 523 (CCPA 1973); *In re Fessmann*, 180 USPQ 324 (CCPA 1974); and *In re Marosi et al.*, 218 USPQ 289 (CAFC 1983) final product per se which must be determined in a "product by, all of" claim, and not the patentability of the

process, and that an old or obvious product, whether claimed in "product by process" claims or not. Note that Applicant has the burden of proof in such cases, as the above case law makes clear

Response to Arguments

7. Applicant's arguments with respect to claims 11-15 & 17-23 have been considered but are moot in view of the new ground(s) of rejection.
8. Applicant's amendment necessitated the new ground(s) of rejection presented in this Office action. Accordingly, **THIS ACTION IS MADE FINAL**. See MPEP § 706.07(a). Applicant is reminded of the extension of time policy as set forth in 37 CFR 1.136(a).

A shortened statutory period for reply to this final action is set to expire THREE MONTHS from the mailing date of this action. In the event a first reply is filed within TWO MONTHS of the mailing date of this final action and the advisory action is not mailed until after the end of the THREE-MONTH shortened statutory period, then the shortened statutory period will expire on the date the advisory action is mailed, and any extension fee pursuant to 37 CFR 1.136(a) will be calculated from the mailing date of the advisory action. In no event, however, will the statutory period for reply expire later than SIX MONTHS from the date of this final action.

Any inquiry concerning this communication or earlier communications from the examiner should be directed to LATANYA CRAWFORD whose telephone number is (571)270-3208. The examiner can normally be reached on Monday-Friday 7:30 AM - 5:00 PM EST.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Carl Whitehead, Jr. can be reached on (571) 272-1702. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see <http://pair-direct.uspto.gov>. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free). If you would like assistance from a USPTO Customer Service Representative or access to the automated information system, call 800-786-9199 (IN USA OR CANADA) or 571-272-1000.

/Carl Whitehead Jr./
Supervisory Patent Examiner, Art Unit 2813

/LaTanya Crawford/
Examiner, Art Unit 2813